



NAR Labs 國家實驗研究院

台灣半導體研究中心

Taiwan Semiconductor Research Institute

GaN Chip Implementation Platform

Hann-Huei Tsai

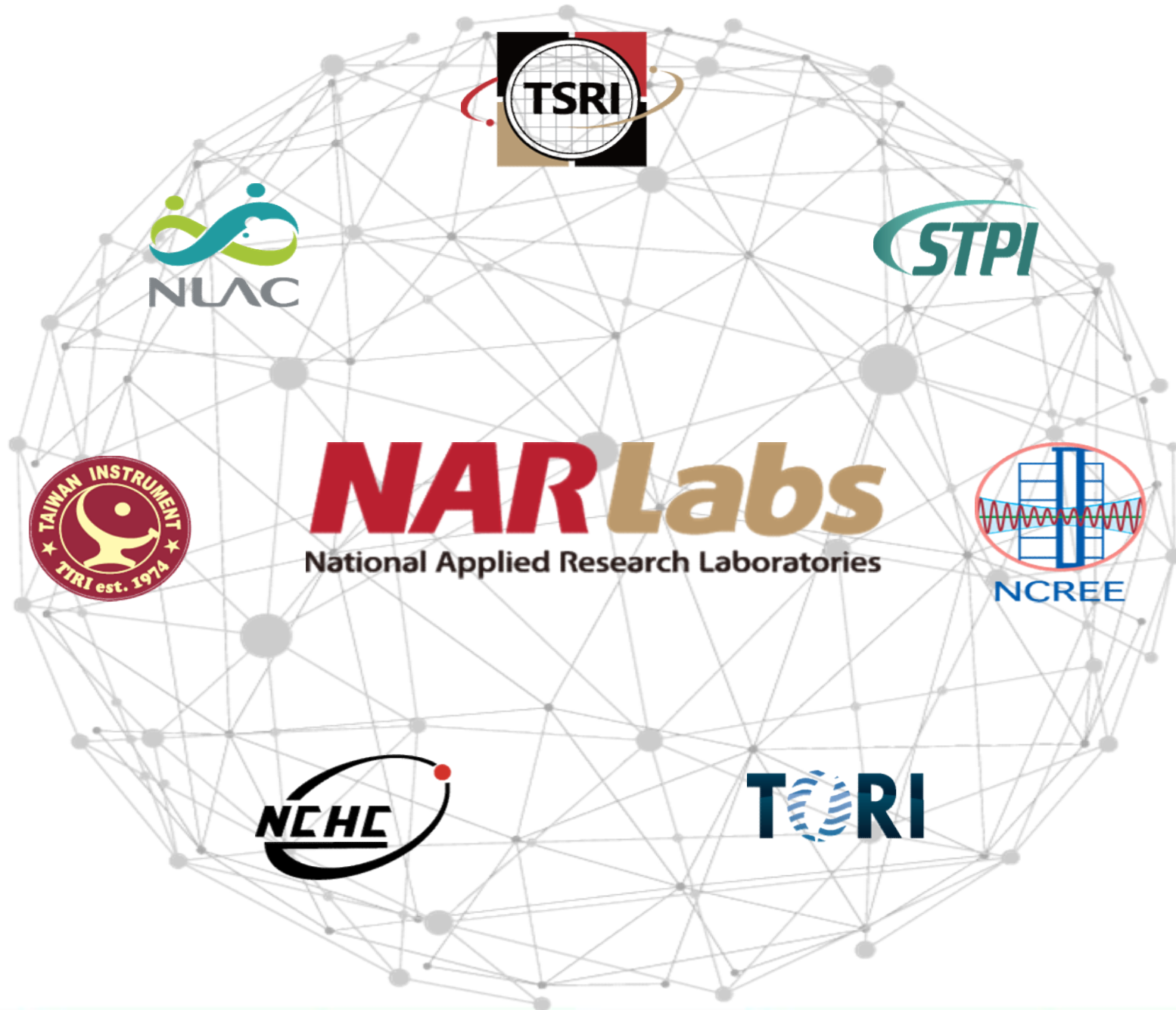
28th September 2023

Outline

- **TSRI Introduction**
- **Process and Design Environment**
- **Heterogeneous Integration**
- **System Verification**
- **Summary**

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TSRI Role and Mission



Cultivate
Talents

Support
Academic Research

Build-up
R&D Platforms

Promote
Advanced Tech.

T

Training

S

Service

R

R&D

I

Innovation

Fill the gap between academia and industry

**Academia
(R+d)**

TSRI
(R+D)

**Industry
(r+D)**

Technical Services



Process & IC Foundry

- Clean Room (~3200m²)
- Class 10 to 10,000
- **Open 24/7 to qualified users**

1,000 students graduated / year

Chip Implementation

- 16nm FinFET
- GaN
- Silicon Photonics

1,800 chips implemented / year
1,200 students graduated / year

Emerging memory/ Advanced Packaging

- Embedded ReRAM, MRAM
- 2.5D/3D, TSV

Semiconductor Manufacture & Design

EDA Cloud Service

- ARM
- Cadence
- Synopsys
- Keysight
- Mentor Graphics

300 R&D teams per year

Electronic & Materials Measurement

- Silicon Photonics / Power & Nano Components
- High frequency/high speed measurement
- MEMS/Electrical Measurement

7,000 cases per year

Training Programs

- Semi-manufactures
- Chip Design & Implementation
- Basic e-learning courses

15,000 person (times) per year

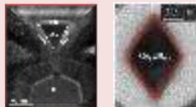
Fabrication Capabilities



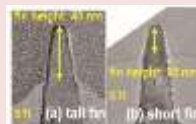
**2.5D、3D、TSV Advanced Packaging/ 3D Heterogeneous Integration/
Circuit Verification (Verification vehicle : Sensor/ Memory)**

Lower power devices (New structure development)

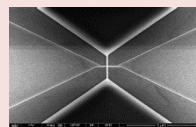
GAA



Non-planar

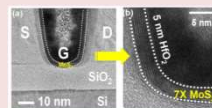


Planar



High speed transistor (Introduction of novel materials)

2D Material



III-V



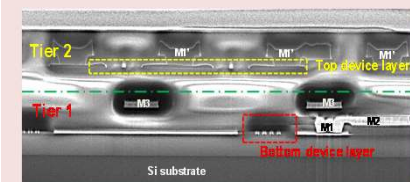
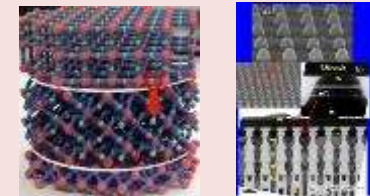
Ge、Ge(Sn)



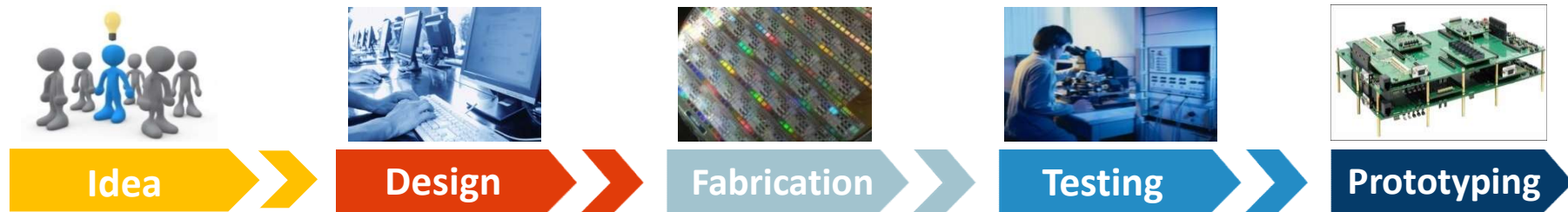
High power devices



Memory (RRAM、MRAM、IMC)



IC Design Service



- Provide IC/system design environments, design flows, and Silicon IPs
 - More than **90 commercial EDA tools from 13 vendors**
 - EDA Cloud Service to optimize the investment and management
- Provide chip fabrication, packaging and PCB production
 - Standard / Advanced / Special-applications
 - Regular processes are available as below:

tsmc 0.35 μ m CMOS
tsmc 0.18 μ m CMOS
tsmc 90nm CMOS
tsmc 40nm CMOS
tsmc 28nm CMOS
tsmc 16nm CMOS
tsmc 7nm CMOS

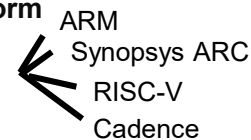
tsmc 0.18 μ m HV CMOS
tsmc 650V GaN

UMC 0.18 μ m CMOS MEMS
Multi-Optional MEMS

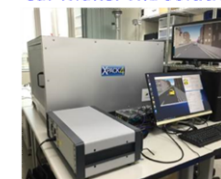
tsmc 0.18 μ m SiGe BiCMOS
WIN 0.15 μ m GaAs pHEMT
WIN 0.25 μ m GaN HEMT

Si-Photonic

- 3 eco-system(Host CPU)
- FPGA platform



Car Maker HIL solution



DGX



Drive PX2



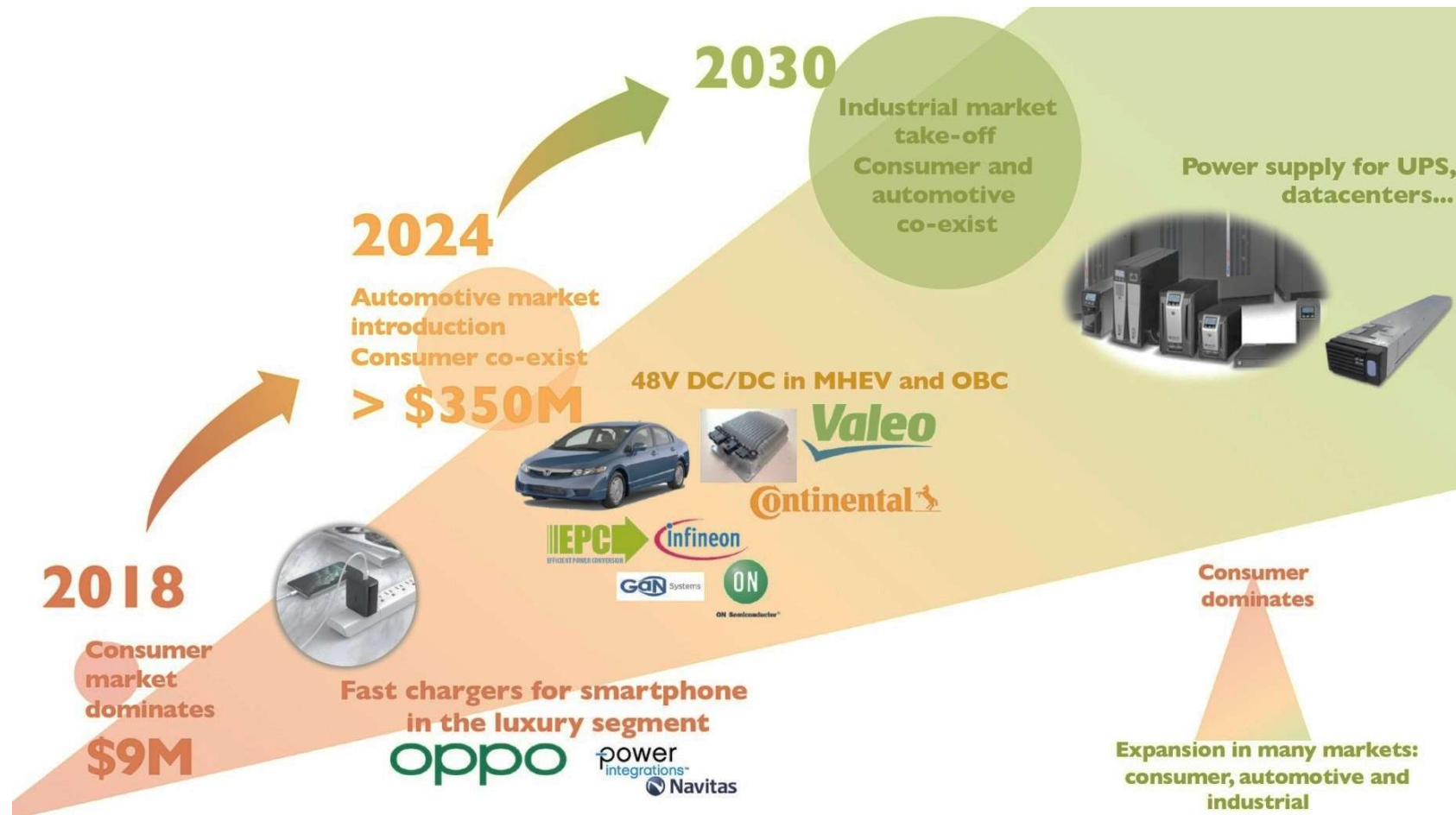
HAPS

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Power GaN Application Fields

- Fast charger applications → industrial & automotive market



Source: Yole

TSMC 650V GaN Process **NAR Labs**

- **Process name:**
TSMC 0.5UM GAN WBG E-HEMT USG AL 0P3M HKMG 650V
 - 650 V power cell
 - 12 V control circuit
- **Suttle service**
 - 2 shuttles/year, 6” full wafer
- **Process advantages**
 - Integration of power device and circuit
 - Low cost of GaN-on-Si

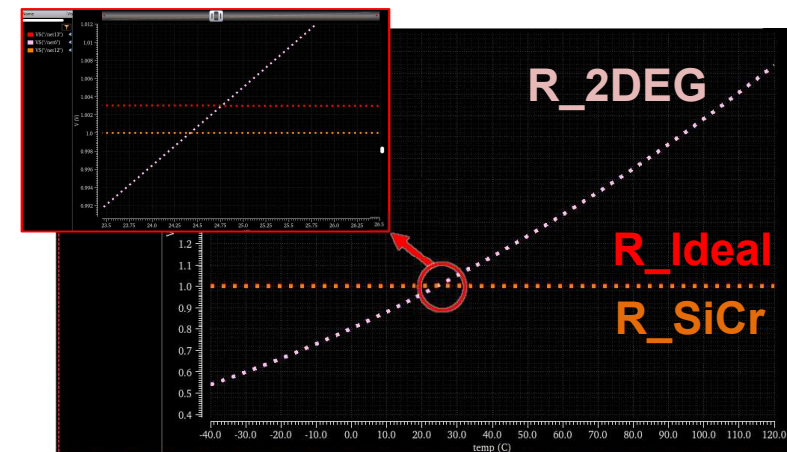
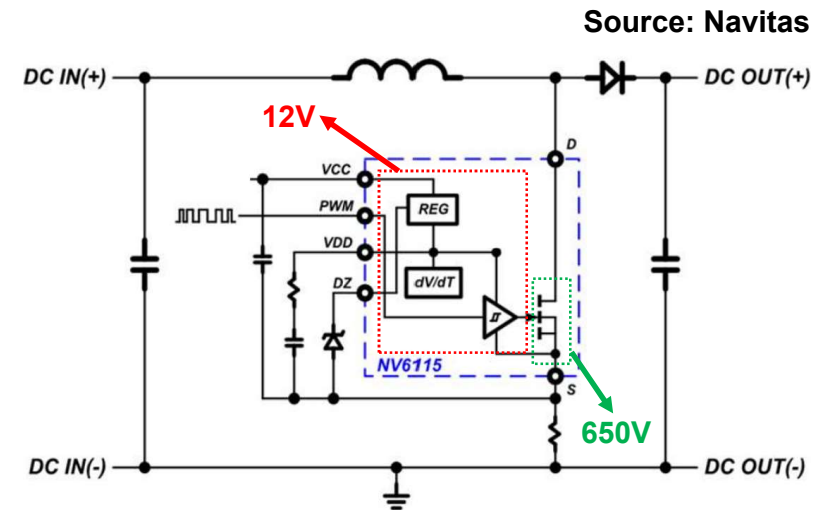
Features of TSMC 650V GaN Process **NAR Labs**

- **Active devices**

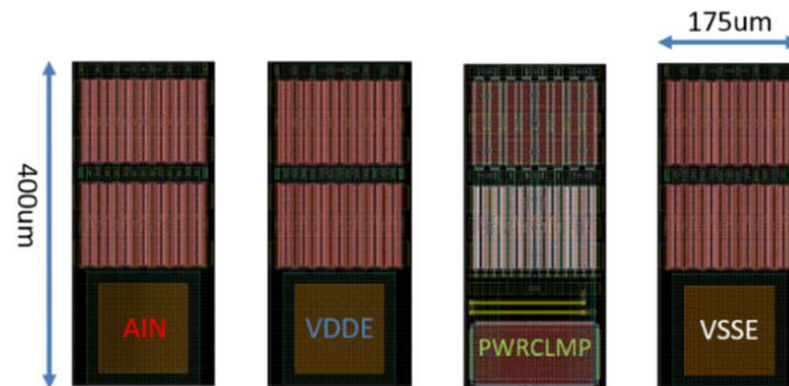
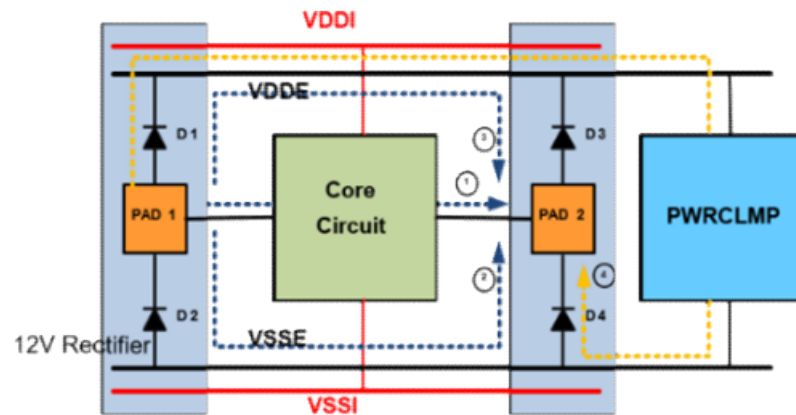
- 650V E-HEMT NMOS
- 12V E-HEMT NMOS
- 12V D-HEMT NMOS
- 12V Rectifier

- **Passive devices**

- P-GaN varactor
- MIM Capacitor
- 2DEG Resistor
- SiCr Resistor



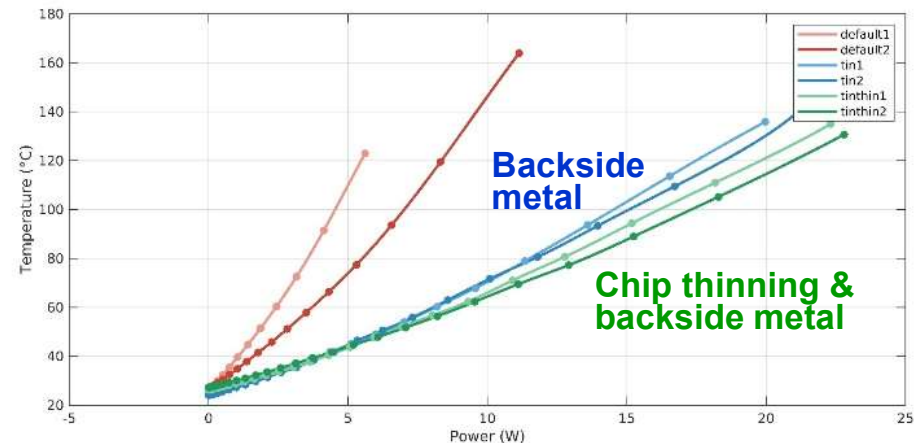
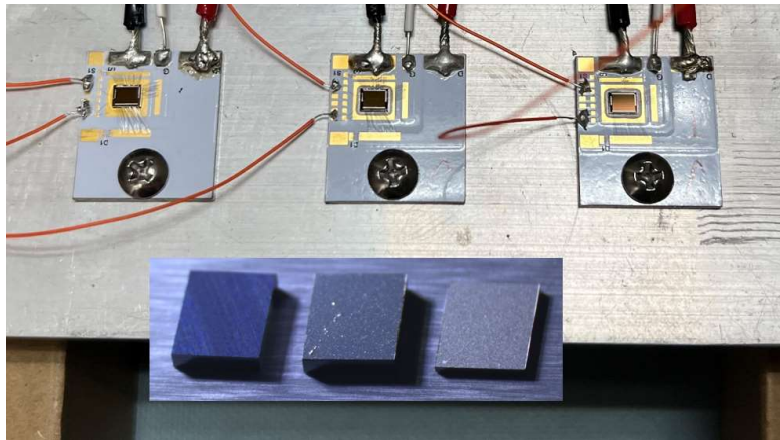
- **ESD protection I/O**
 - VDDE/VSSE/AIN/PWRCLMP
 - 400 μm x 175 μm



TSRI Developing Techniques cont. **NAR Labs**

- **Thermal dissipation improvement**

- Chip thinning
- Backside metal
- Chip thinning & backside metal



GaN Research Topics by TSRI Customers

- **Device development/improvement**
 - ESD protection device
 - Schottky diode
 - GaN transistor characterization
 - Temperature effect
- **High integration circuits of T50GaN**
 - High switching frequency
 - DC/DC converter
 - gate driver
 - High power density
 - power amplifier
 - power switch
 - Oscillator
 - ESD protection circuit

Prospective Research Competitiveness

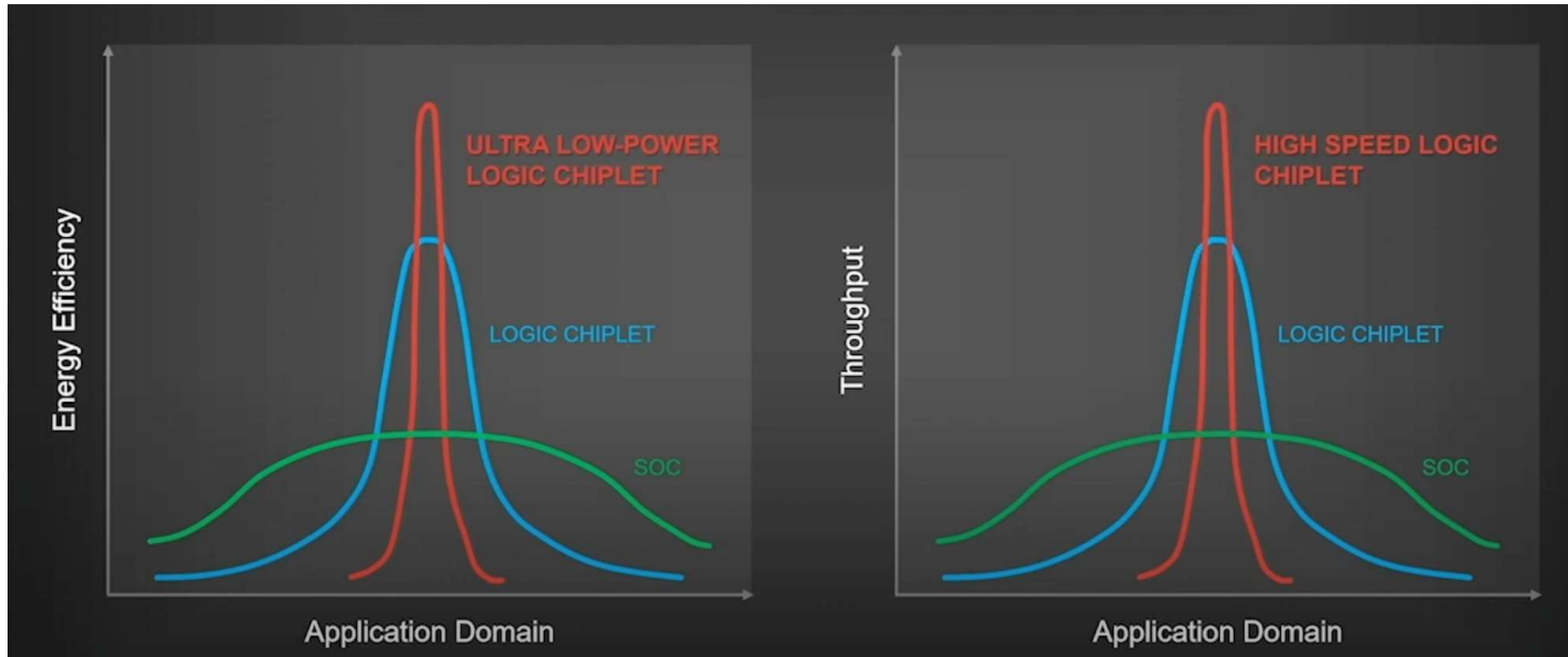
- TSRI is **ONLY** the institute provided TSMC GaN process to academia in the world
- Regular GaN session in **ISSCC from 2017**

ISSCC 2017	
25 GaN Drivers and Galvanic Isolators.....	426
ISSCC 2018	
24 GaN Drivers and Converters.....	380
ISSCC 2019	
15 Power for 5G, Wireless Power, and GaN Converters.....	236
ISSCC 2020	
18 GaN & Isolated Power Conversion.....	284
ISSCC 2021	
33 High-Voltage, GaN and Wireless Power.....	458
ISSCC 2022	
14 GaN, High-Voltage and Wireless Power.....	226
ISSCC 2023	
20 GaN Power Conversion.....	300

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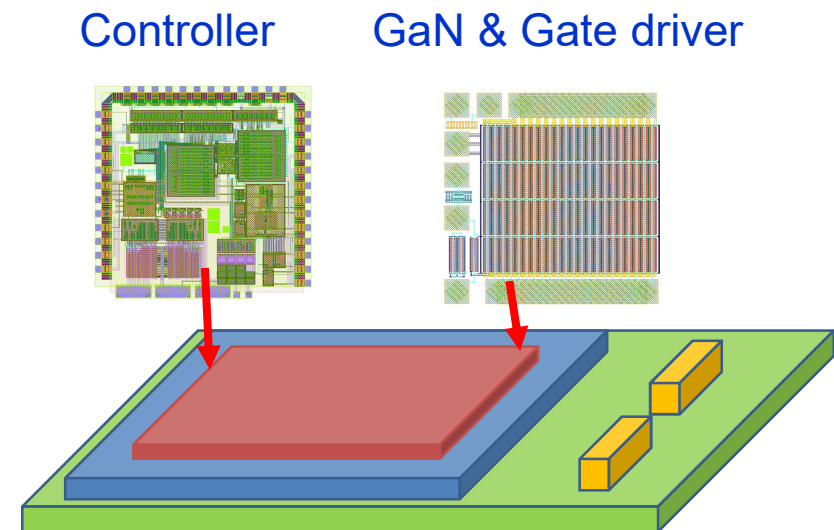
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Go Beyond Individual Chips



Chiplets in Power Module

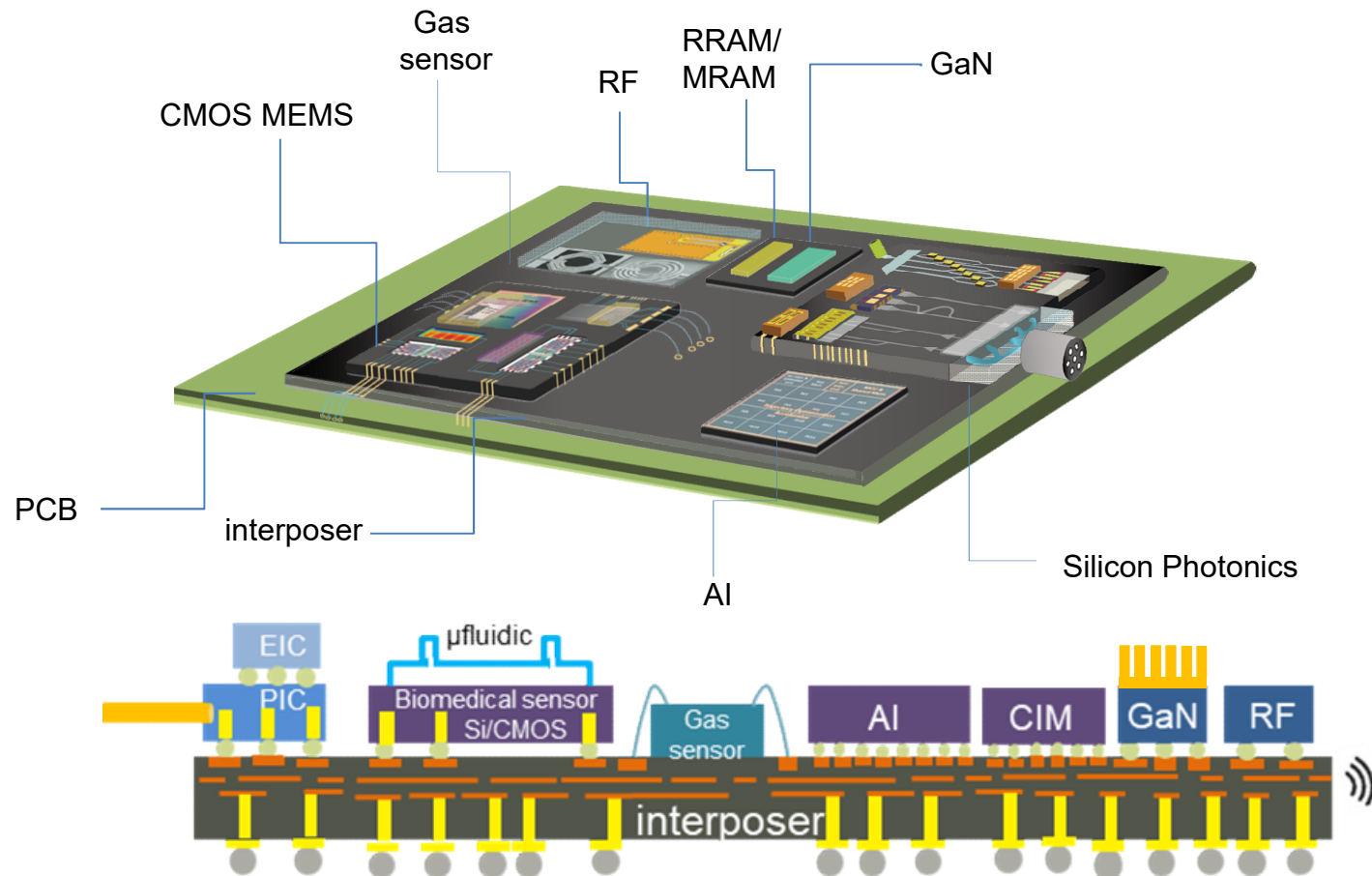
- **Combined advantages of Silicon and GaN**
 - Si
 - CMOS/BCD
 - Complicate control capability
 - Low static loss
 - GaN
 - High switching frequency
 - High power density



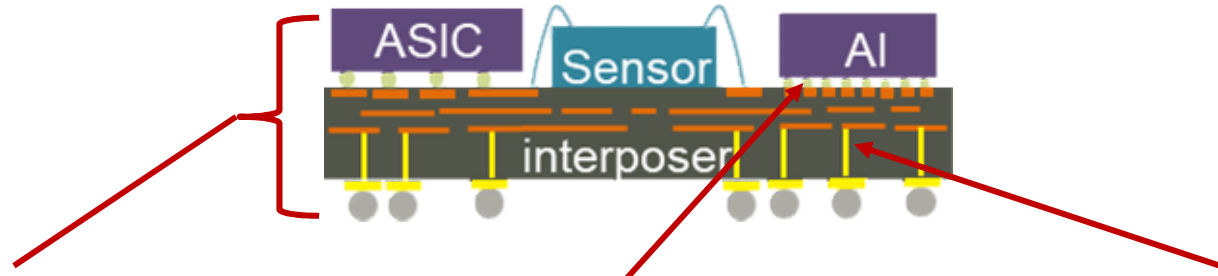
Competitive in small and high-power density

TSRI 2.5D/3D Heterogeneous Integration

- Integrate advanced ICs, Optoelectronics/MEMS/biomedical sensors, CIM, power managements, wireless/photonic communications
- A platform for academia and startups to verify their prototypes

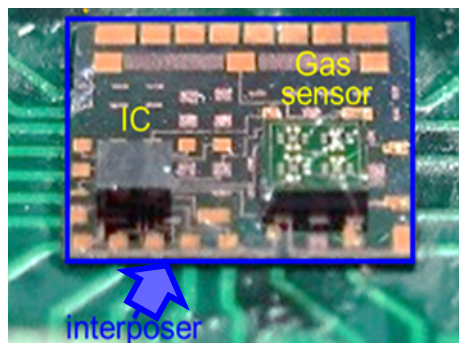


Key Technologies



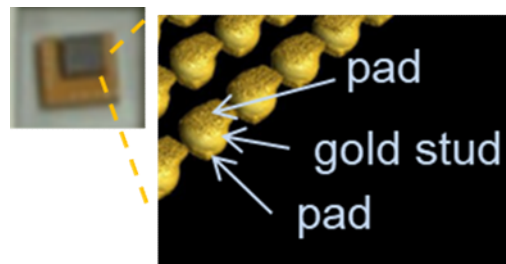
CoCoP

- Now providing services to academia



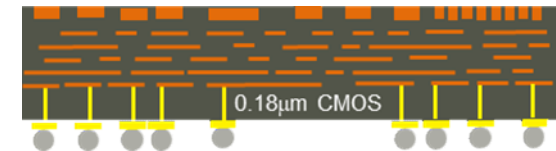
Die-level 50 μm -pitch microbump

- 2023: Verification
- 2024: Start servicing



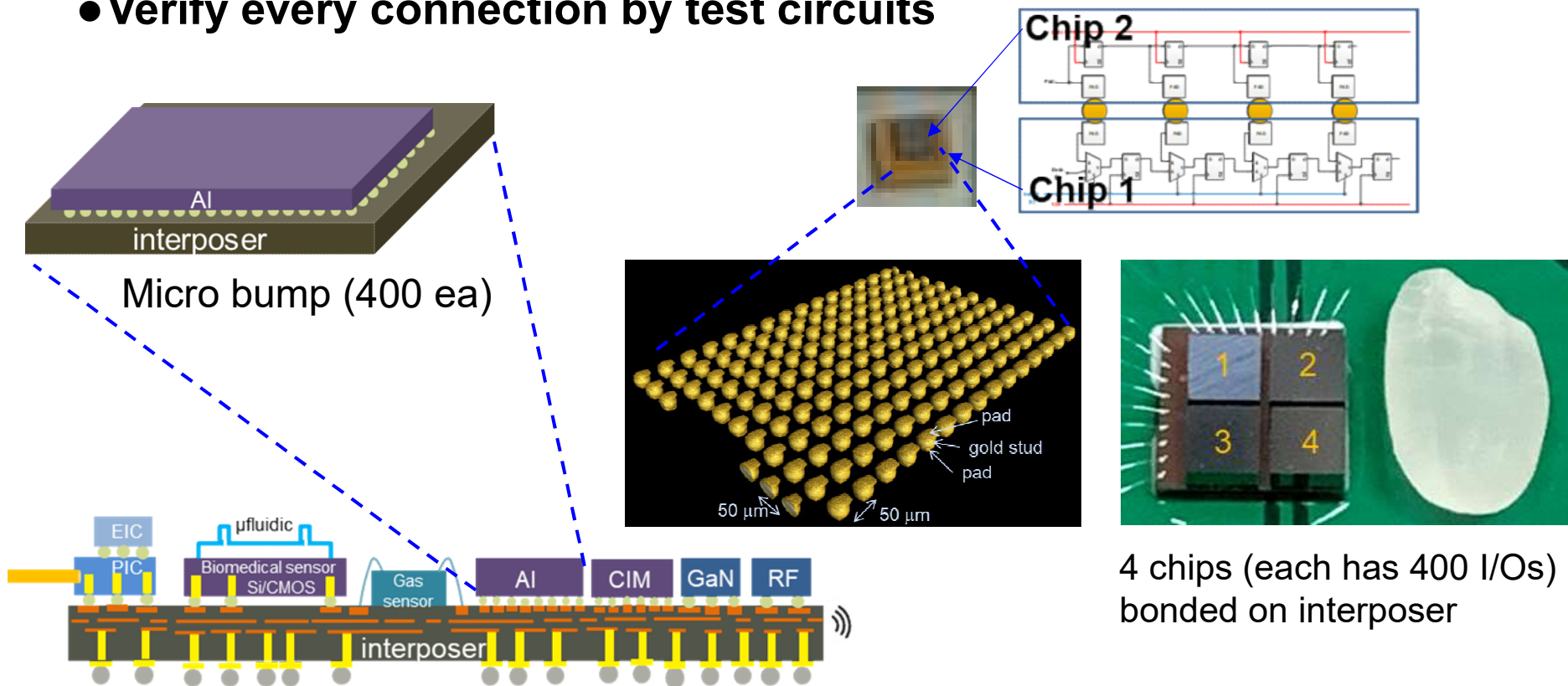
CMOS BS TSV

- 2023~2024: Development and verification
- 2025: Start servicing



Die-level μ bump Technology

- Motivation: High cost to have 16/28 nm wafers with micro bumps
- Goal: Realize the 50 μ m pitch micro bump in the AI chiplet with >100 I/Os
- Verify every connection by test circuits

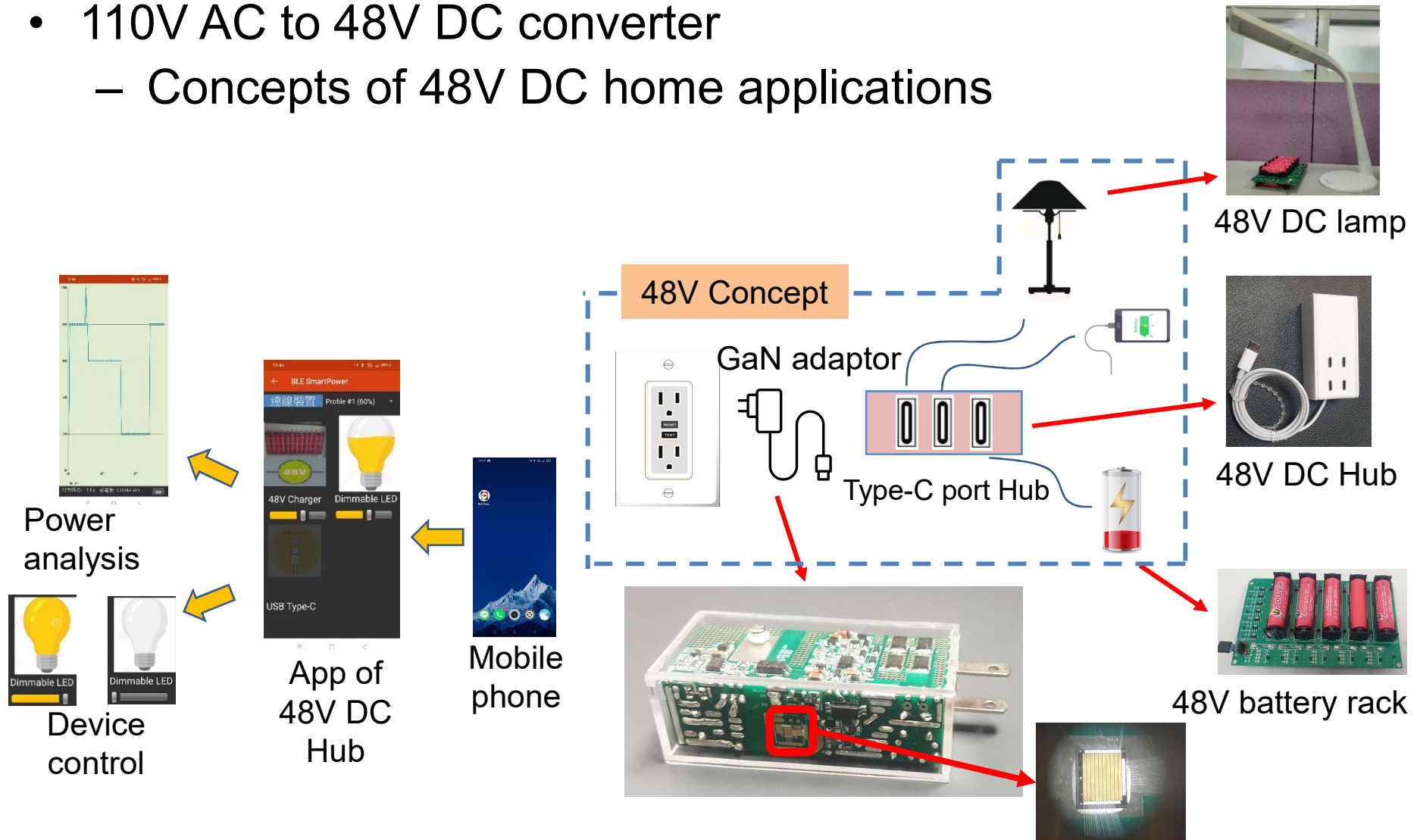


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Demonstration of GaN Chip

- 110V AC to 48V DC converter
 - Concepts of 48V DC home applications



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Summary

- **Make innovative GaN devices in TSRI**
- **Design unique GaN ICs in TSRI**
- **Realize smart GaN power modules by TSRI HI Technology**
- **Welcome international collaborations!**

The logo for NAR Labs is located in the top-left corner of the slide. It consists of the text "NAR Labs" in a white, bold, sans-serif font, set against a background of overlapping geometric shapes in various shades of orange and red.

NAR Labs

Thanks for your attention!

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